



## SILICON NITRIDE SPUTTERING TARGET

Silicon nitride ( Si<sub>3</sub>N<sub>4</sub> ) is a chemical compound which consists of the elements silicon and nitrogen. Silicon nitride sputtering targets are used for CD-ROM, decoration, semiconductor, display, LED and photovoltaic devices, functional coating as nicely as other optical information storage space industry, glass coating industry like car glass and architectural glass, optical communication, etc. Silicon nitride has also been used in high-temperature applications, such as rocket engines. It was considered as one of the few monolithic ceramic materials that could survive the severe thermal shock and thermal gradients generated in hydrogen-oxygen rocket engines.

### Quick Facts

Product	:	Silicon Nitride Sputtering Target
Stock No	:	NS6130-10-1058
CAS	:	12033-89-5
Backing Plate	:	(As per Customer requirement)

### Additional Characteristics

Stock No.	Purity	Diameter	Thickness
NS6130-10-1058	99.99%	50.8 mm ± 1mm	3 mm ± 0.5mm

### Technical Specification

Molecular Formula	Molecular Weight	Melting Point
Si <sub>3</sub> N <sub>4</sub>	140.28g/mol	1900°C



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 ISO 9001:2015  
 CERTIFIED COMPANY

 High Purity  
 SPUTTERING  
 TARGET